

REVERSE TONE PROCESS FOR MASKS

ABSTRACT OF THE DISCLOSURE

5 A reverse image mask is produced by initially depositing a metallic layer on a substrate. Resist is applied to the metallic layer to pattern desired features. The metallic layer is plated with a metal film, and the resist is then stripped. The metallic layer is etched using the metal film as a mask. Finally, the metal film is etched leaving the metallic layer etched in patterned areas to provide the reverse image mask.